In response to the Office Action dated March 4, 2003 kindly amend the subject application as follows:

b.) Amendments to the Specification:

Please amend the specification on page 80, lines 7-19 to read as follows:

- - Examples of the mechanical impact application apparatus may include: mechanical pulverizers, such as ~~Krypron System~~ "KRYOPRON SYSTEM" (made by Kawasaki Jukogyo K.K.) and ~~"Trubomill"~~ "TURBOMILL" (made by Turbo Kogyo K.K.), and mechanical impacting devices, such as ~~"Mechanofusion System"~~ "MECHANOFUSION SYSTEM" (made by Nara Kikai Seisakusho K.K.) and ~~"Hybridization System"~~ "HYBRIDIZATION SYSTEM" (made by Nara Kikai Seisakusho K.K.) wherein toner particles are pressed against an inner wall of a casing under action of a centrifugal force exerted by blades stirring at high speeds, thereby applying mechanical impact forces including compression and abrasion forces to the toner particles. - -

Please amend the specification on page 108, line 6 to page 109, line 11 to read as follows:

- - The particle size distributions and average particle sizes may be measured by using, e.g., Coulter Counter Model TA-II or Coulter ~~Multicizer~~ MULTISIZER (respectively available from Coulter Electronics, Inc.). Herein, these values are determined based on values measured by using Coulter ~~Multicizer~~ MULTISIZER connected to an interface (made by Nikkaki K.K.) and a personal computer ("PC9801", made by NEC K.K.) for providing a number-basis distribution and a volume-basis distribution in the following manner. A 1%-

aqueous solution is prepared as an electrolytic solution by sing a reagent-grade sodium chloride (it is also possible to use ISOTON R-II (available from Coulter Scientific Japan K.K.)). For the measurement, 0.1 to 5 ml of a surfactant, preferably a solution of an ~~alkylbenzenesulfonic acid salt, is added a a dispersant into 100 to 150 ml of the electrolytic~~ solution, and 2-20 mg of a sample toner is added thereto. The resultant dispersion of the sample in the electrolytic solution is subjected to a dispersion treatment for ca. 1-3 minutes by means of an ultrasonic disperser, and then subjected to measurement of particle size distribution in the range of 2.00 - 40.30 μm divided into 13 channels by using the above-mentioned Coulter counter with a 100 μm- aperture to obtain a volume-basis distribution and a number-basis distribution. From the volume-basis distribution, a weight-average particle size (D4) and a volume-average particle size (Dv) are calculated by using a central value as a representative value channel. From the number-basis distribution, a number-average particle size (D1) and a number-basis variation coefficient (S1) is calculated.- -

Please amend the specification on page 119, lines 9-12 to read as follows:

- - The cells may preferably have concavities providing an average cell diameter corresponding to spheres of 5 - 300 μm and also a void areal percentage at the surface of 15 - 90 %.- -

Please amend the specification on page 130, line 23 to page 131, line 4 to read as follows:

- - The AC voltage may preferably have a peak voltage of ~~blow~~ below 2 x Vth (Vth: discharge initiation voltage at the time of DC voltage application). If this condition is not satisfied, the potential on the image-bearing member is liable to be unstable. The AC voltage applied in superposition with a DC voltage may more preferably have a peak

voltage below Vth so as to charge the image-bearing member without being substantially accompanied with a discharge phenomenon. - -

Please amend the specification on page 133, line 26 to page 134, lines 5 to ~~read as follows:~~

- - The classification method and apparatus used for production of magnetic particles are not particularly limited. In order to obtain a desired particle size efficiently, it is preferred use a sloped inertia classifier such as ~~"Elbow Jet"~~ "ELBOW JET", a centrifugal ~~separater~~ separator, such as ~~"Dispersion Separator"~~ "DISPERSION SEPARATOR"or "Turboplex" "TURBOPLEX", or sieving.- -

Please amend the specification on page 148, lines 6 - 10 to read as follows:

- - During the formation of the photoconductor layer 203, the electroconductive support ~~21~~ 201 may be held at an optimally set temperature, preferably 200 - 350 ˚C, more preferably 230 - 330 ˚C, further preferably 250 - 310 ˚C. - -

Please amend the specification on page 148, line 26 to page 149, line 10 to read as follows:

- - The surface layer ~~24~~ 204 may comprise any non-single crystal material. For example, the surface layer may comprise: amorphous silicon containing hydrogen (H) and/or halogen (X) and further carbon (C) (denoted by "a-SiC:H,X"), amorphous silicon containing hydrogen (H) and/or halogen (X) and further oxygen (O) (denoted by "a-SiO:H,X"), amorphous silicon containing hydrogen (H) and/or halogen (X and further nitrogen (N) (denoted by "a-SiN:H,X"), and amorphous silicon containing hydrogen (H) and/or halogen (X) and further at least one of carbon (C), oxygen (O) and nitrogen (N) (denoted by "a-SiCON:H,X").- -

Please amend the specification on page 160, line 26 to page 161, line 12, to read as follows:

- - The surface roughness (Ra) values described herein are based on values ~~measured as center line-average roughness values by using a surface roughness meter (“Surfcorder SE-3OH”~~ “SURFCORDER SE-3OH”, available from K.K. Kosaka Kenkyusho) according to JIS B-0601. More specifically, based on a surface roughness curve obtained for a sample surface, a length of a is taken along a center line of the roughness curve. The roughness curve is represented by a function Y = f(x) while setting the X-axis on the center line and a roughness scale (y) on the Y-axis along the length x portion. A center line-average roughness Ra of the roughness curve is determined by the following formula:- -